

## MNF Instrument Fees

| No. | MNF name  | Booking system name  | Fee €/h   |                           |          | Location     |      |
|-----|---|--|-----------|---------------------------|----------|--------------|------|
|     |   |  | Academic* | Service /Academic, ext. * | Industry | CenTech/ SoN | Area |
| 1   | Scanning Near-Field Optical Microscopy (SNOM) - neaSNOM                                     | neaSNOM  | 50        | 100                       | 150      | SoN          | Lab  |
| 2   | JFK AFM   | JFK AFM  | 50        | 100                       | 150      | SoN          | Lab  |
| 3   | Atomic Force Microscopy (AFM)- Bruker- Bioscope   | Nanoscope AFM  | 50        | 100                       | 150      | SoN          | Lab  |
| 4   | Atomic Force Microscopy (AFM)- JFK  | Bioscope AFM   | 50        | 100                       | 150      | SoN          | Lab  |
| 5   | Dual beam Si/Au Focus Ion Beam (FIB)/ SEM - Raith VELION                                    |  | 80        | 120                       | 200      | SoN          | Lab  |
| 6   | Time-of-Flight- Secondary Ion Mass Spectroscopy (ToF-SIMS) - Cryo-IONTOF M6 Special Edition | ToF SiM  | 80        | 120                       | 200      | SoN          | Lab  |
| 7   | Plasma Enhanced Chemical Vapour Deposition (PECVD) - Oxford Plasmalab 80+                   | OXFORD PECVD   | 50        | 100                       | 150      | SoN          | CR   |
| 8   | Reactive Ion Etcher (RIE) - Oxford PlasmaPro 80   | Oxford 80 RIE  | 50        | 100                       | 150      | SoN          | CR   |
| 9   | Inductively Coupled Reactive Ion Etcher (ICP RIE) - Oxford PlasmaPro 100                    | Oxford 100 ICP   | 50        | 100                       | 150      | SoN          | CR   |
| 10  | Plasma Asher- Diener Zepto-W6   | Plasma Asher - Diener ZEPTO-W6                                 | 0         | 0                         | 0        | SoN          | CR   |
| 11  | Helium/Neon Focused Ion Beam (FIB) – Zeiss ORION NanoFab                                    | Orion Nanofab He/Ne FIB  | 80        | 140                       | 200      | SoN          | CR   |
| 12  | Dual Beam microscope (SEM / FIB)- Zeiss CrossBeam 340                                       | Zeiss Cross Beam 340 SEM/FIB                                   | 80        | 140                       | 200      | SoN          | CR   |
| 13  | Nano Imprint Lithography System - EVG620 NT   | EVG620 NT - Nano Imprint Lithography System                    | 50        | 100                       | 150      | SoN          | CR   |
| 14  | Photoresist wet bench   | Wetbench spin coating  | 0         | 0                         | 0        | SoN          | CR   |
| 15  | Organic material wet bench  | Wetbench organic chemistry                                     | 0         | 0                         | 0        | SoN          | CR   |
| 16  | Beam pen lithography- TERA-print  | Dip Pen  | 50        | 100                       | 150      | SoN          | CR   |
| 17  | Polymer pen lithography- n.able Molecular Printer   | Polymer Pen Lithography_ n.able                                | 50        | 100                       | 150      | SoN          | CR   |
| 18  | Film thickness measurement system- Toho Spec 3100   | Toho ellipsometer  | 0         | 0                         | 0        | SoN          | CR   |
| 19  | Acids wet bench   | Wet bench acid   | 0         | 0                         | 0        | SoN          | CR   |
| 20  | Base wet bench  | Wet bench base   | 0         | 0                         | 0        | SoN          | CR   |
| 21  | Dual Beam microscope (SEM / FIB) - Zeiss XB1540 Crossbeam                                   | Scanning Electron Microscope (SEM) and Focussed Ion Beam (FIB) | 50        | 100                       | 150      | CenTech      | Lab  |
| 22  | Chemical-Mechanical Polisher (CMP)- Logitech Tribo-1018                                     | CMP 1  | 50        | 100                       | 150      | CenTech      | Lab  |
| 23  | Lapping and polishing system- Logitech PM6  | CMP 2 (PM6)  | 50        | 100                       | 150      | CenTech      | Lab  |
| 24  | Transmission Electron Microscope (TEM)- Thermo Fisher Scientific FEI TITAN Themis G3 60-300 | Titan Themis TEM   | 120       | 200                       | 300      | CenTech      | Lab  |
| 25  | Semi-automatic dicing system - K&S 7100 ad  | Dicing System  | 50        | 100                       | 150      | CenTech      | Lab  |
| 26  | Atomic Layer Deposition (ALD) - Cambridge NanoTech Savannah                                 | ALD  | 50        | 100                       | 150      | CenTech      | Lab  |
| 27  | Physical Vapor Deposition (PVD)- Edwards Auto 306   | EB-Thermo PVD  | 50        | 100                       | 150      | CenTech      | Lab  |
| 28  | Electron Beam Physical Vapor Deposition (EB-PVD)  | Physical Vapour Deposition (PVD)                               | 50        | 100                       | 150      | CenTech      | CR   |
| 29  | Sputtering system - Aja Orion 8 UHV   | AJA Sputter Tool   | 50        | 100                       | 150      | CenTech      | CR   |
| 30  | Sputtering system - von Ardenne LS 730S   | Von Ardenne Sputter System                                     | 50        | 100                       | 150      | CenTech      | CR   |
| 31  | 3D Lithography - Nanoscribe Photonic Professional GT  | Nanoscribe Photonic Professional GT                            | 50        | 100                       | 150      | CenTech      | CR   |
| 32  | Plasma Asher - Dionex 2000 Plasma System  | Plasma Asher - Dionex  | 0         | 0                         | 0        | CenTech      | CR   |
| 33  | Sputterer Au  | Sputterer Au   | 0         | 0                         | 0        | CenTech      | CR   |
| 34  | Resist spin coaters - POLOS Spin 150i SPS europe  | Spin Coater Wet-Bench (EBeam resist)                           | 0         | 0                         | 0        | CenTech      | CR   |
| 35  | General polymer spin coater - Convac TSR48/5 1QS  | Spin Coater Fumehood (Photoresist)                             | 0         | 0                         | 0        | CenTech      | CR   |
| 36  | E-beam preparation wet bench  | Spin Coater Photoresist  | 0         | 0                         | 0        | CenTech      | CR   |
| 37  | Mask aligner - Karl Suss MA56   | Mask Aligner   | 0         | 0                         | 0        | CenTech      | CR   |
| 38  | Scanning Electron Microscope (SEM) - JEOL JSM-IT100   | JEOL SEM   | 30        | 60                        | 100      | CenTech      | CR   |
| 39  | Ellipsometer - Woolam M-2000  | Woolam Ellipsometer  | 0         | 0                         | 0        | CenTech      | CR   |
| 40  | Critical Point Dryer - Leica EM CPD300  | Critical Point Dryer   | 30        | 60                        | 100      | CenTech      | Lab  |
| 41  | Inductively Coupled Plasma Reactive Ion Etcher (ICP-RIE) - MicroSys200                      | RIE- Micro sys 200   | 50        | 100                       | 150      | CenTech      | CR   |
| 42  | Electron beam lithography - Raith EBPG5150  | Raith EBPG 100kV Ebeam   | 80        | 120                       | 200      | SoN          | CR   |
| 43  | Tube furnace - Nabertherm R 120/500/13  | Tube Furnace   | 0         | 0                         | 0        | CenTech      | Lab  |
| 44  | Wire bonder - tpt HB10  | Wire Bonder  | 0         | 0                         | 0        | CenTech      | Lab  |
| 45  | Film thickness measurement system- Toho Spec 3100   | Toho Spec 3100   | 0         | 0                         | 0        | SoN          | CR   |